

Attorney's Docket No. 027260-295

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

## In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

**Filed: May 26, 1999**

For: PHOTOMASK, FABRICATION  
METHOD OF PHOTOMASK, AND  
FABRICATION METHOD OF  
SEMICONDUCTOR INTEGRATED  
CIRCUIT



**Group Art Unit: 1756**

**Examiner: S. Mohamedulla**

**AMENDMENT UNDER 37 C.F.R. §1.116**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Date: March 2, 2001

Sir:

This amendment responds to the Office Action dated December 5, 2000

(Paper No. 6). Please amend the above-noted application as follows:

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MAR -5 2001  
TC 1700 MAIL ROOM

**IN THE CLAIMS:**

~~Please~~ replace claims 7 and 28 as follows:

7. ~~(Twice Amended)~~ A photomask comprising:

a transparent substrate;

a hollow section formed on a surface of said transparent substrate;

a shade pattern made up of a shade film, said shade film formed in said hollow section; and

a phase shift pattern formed by etching said transparent substrate including said shade pattern formed in said hollow section.

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